

Title (en)

METHOD OF PREPARING OPTICALLY IMAGED HIGH PERFORMANCE PHOTOMASKS

Title (de)

VERFAHREN ZUR HERSTELLUNG VON OPTISCH BEBILDERTEN HOCHLEISTUNGSPHOTOMASKEN

Title (fr)

PROCEDE DE PREPARATION DE PHOTOMASQUES A PERFORMANCE ELEVEE A IMAGE OPTIQUE

Publication

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Application

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Abstract (en)

[origin: WO03010601A1] One principal embodiment of the disclosure pertains to a method of optically fabricating a photomask using a direct write continuous wave laser, comprising a series of steps including: applying an organic antireflection coating over a surface of a photomask which includes a chrome-containing layer; applying a chemically-amplified DUV photoresist over a specific temperature range; exposing a surface of the DUV photoresist to the direct write continuous wave laser; and, post exposure baking the imaged DUV photoresist over a specific temperature range. The direct write continuous wave laser preferably operates at a wavelength of 244 nm or 257 nm. In an alternative embodiment, the organic antireflection coating may be applied over an inorganic antireflection coating which overlies the chrome containing layer.

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IPC 8 full level

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